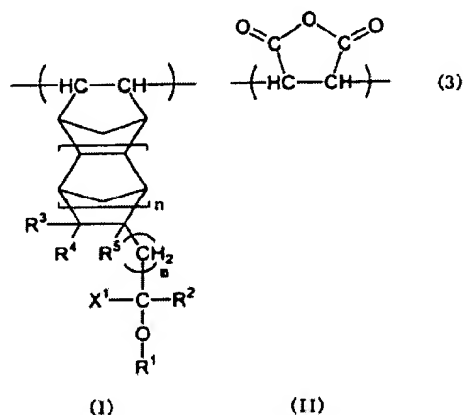


IN THE CLAIMS

1 - 4 (Cancel)

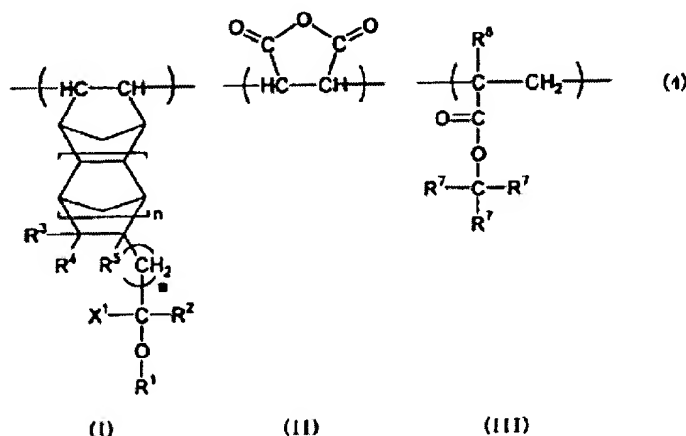
5. (Previously Presented) A radiation-sensitive resin composition comprising (A) an alkali insoluble or scarcely soluble acid-labile group-containing resin having a recurring unit (I) and a recurring unit (II) shown by the following formula (3) and (B) a photoacid generator:



wherein R¹ represents a hydrogen atom, a monovalent acid-labile group, an alkyl group having 1-6 carbon atoms which does not have an acid-labile group, or an alkylcarbonyl group having 2-7 carbon atoms which does not have an acid-labile group, X¹ represents a linear or branched fluorinated alkyl group having 1-4 carbon atoms, R² represents a hydrogen atom, a linear or branched alkyl group having 1-10 carbon atoms, or a linear or branched fluorinated alkyl group having 1-10 carbon atoms, R³, R⁴, and R⁵ individually represents a hydrogen atom or a linear or branched alkyl group having 1-4 carbon atoms, a monovalent oxygen-containing polar group, or a monovalent nitrogen-containing polar group, n is an integer of 0-2, and m is an integer of 0-3.

6. (Original) The radiation-sensitive resin composition according to Claim 5, wherein the content of the recurring unit (I) in the resin component (A) is 1-50 mol% of the total amount of recurring units.

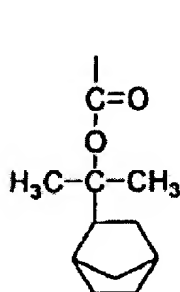
7. (Previously Presented) A radiation-sensitive resin composition comprising (A) an alkali insoluble or scarcely soluble acid-labile group-containing resin (A) having a recurring unit (I), a recurring unit (II), and a recurring unit (III) shown by the following formula (4):



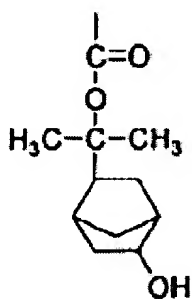
wherein R^1 represents a hydrogen atom, a monovalent acid-labile group, an alkyl group having 1-6 carbon atoms which does not have an acid-labile group, or an alkylcarbonyl group having 2-7 carbon atoms which does not have an acid-labile group, X^1 represents a linear or branched fluorinated alkyl group having 1-4 carbon atoms, R^2 represents a hydrogen atom, a linear or branched alkyl group having 1-10 carbon atoms, or a linear or branched fluorinated alkyl group having 1-10 carbon atoms, R^3 , R^4 , and R^5 individually represents a hydrogen atom or a linear or branched alkyl group having 1-4 carbon atoms, a monovalent oxygen-containing polar group, or a monovalent nitrogen-containing polar group, n is an integer of 0-2, m is an integer of 0-3, R^6 represents a hydrogen atom or methyl group, and R^7 individually represents a linear or branched alkyl group having 1-4 carbon atoms or a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, or any two of R^7 's form in combination with a divalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, with the remaining R^7 being a linear or branched alkyl group having 1-4 carbon atoms or a monovalent alicyclic

hydrocarbon group having 4-20 carbon atoms or a derivative thereof.

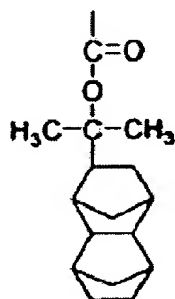
8. (Original) The radiation-sensitive resin composition according to Claim 7, wherein the group $-\text{COO}-\text{C}(\text{R}^7)_3$ in the recurring unit (III) of the formula (4) is at least one group selected from the group consisting of t-butoxycarbonyl group, 1-methylcyclopentyloxycarbonyl group, 1-methylcyclohexyloxycarbonyl group, and the groups represented by the following formulas (ii-1), (ii-2), (ii-10), (ii-11), (ii-13), (ii-14), (ii-16), (ii-17), (ii-22), (ii-23), (ii-34), (ii-35), (ii-40),



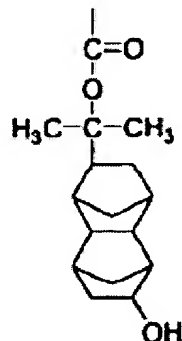
(ii-1)



(ii-2)

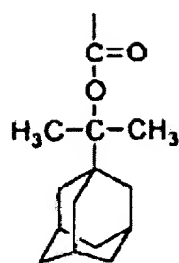


(ii-10)

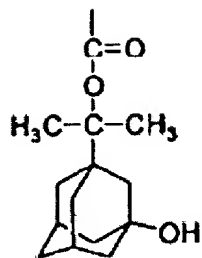


(ii-11)

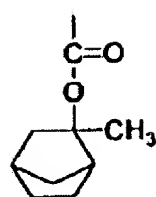
(ii-41), (ii-52), or (ii-53).



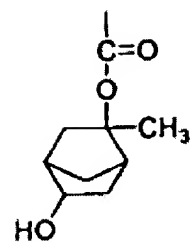
(ii-13)



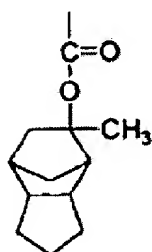
(ii-14)



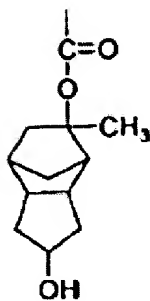
(ii-16)



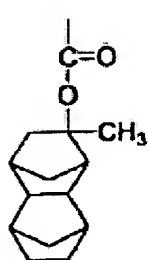
(ii-17)



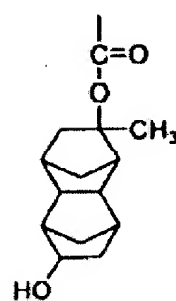
(ii-22)



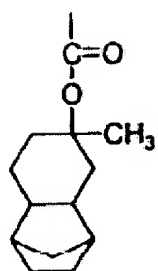
(ii-23)



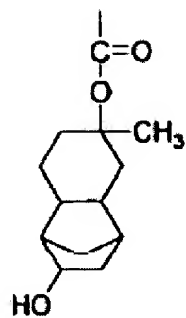
(ii-34)



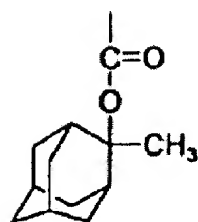
(ii-35)



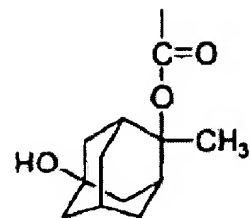
(ii-40)



(ii-41)



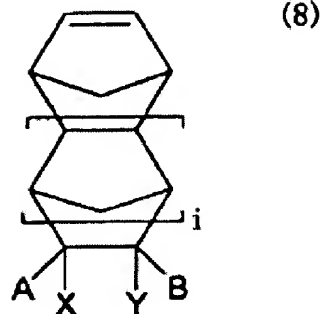
(ii-52)



(ii-53)

10. (Original) The radiation-sensitive resin composition according to Claim 9, wherein

a compound of the following formula (8)



wherein either one of A and B or both are a t-butoxycarbonyl group, 1-methylcyclopentylloxycarbonyl group, 1-methylcyclohexylloxycarbonyl group, or the group shown by the formulas (ii-1), (ii-2), (ii-10), (ii-11), (ii-13), (ii-14), (ii-16), (ii-17), (ii-22), (ii-23), (ii-34), (ii-35), (ii-40), (ii-41), (ii-52), or (ii-53), the remainder of the A and B, X, and Y are a hydrogen atom, and i is 0;

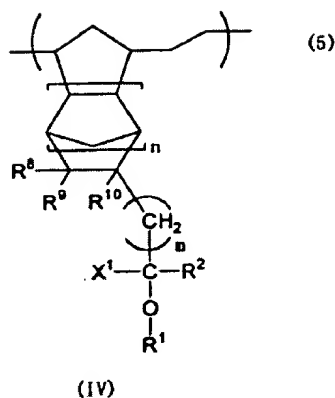
a compound of the formula (8) in which either one of A and B or both are a t-butoxycarbonyl group, 1-methylcyclopentylloxycarbonyl group, 1-methylcyclohexylloxycarbonyl group, or the group shown by the formulas (ii-1), (ii-2), (ii-10), (ii-11), (ii-13), (ii-14), (ii-16), (ii-17), (ii-22), (ii-23), (ii-34), (ii-35), (ii-40), (ii-41), (ii-52), or (ii-53), the remainder of the A and B, X, and Y are a hydrogen atom, and i is 1; and

5,6-di (t-butoxycarbonylmethoxycarbonyl)bicyclo [2.2.1] hept-2-ene,

8-methyl-8-t-butoxycarbonyltetracyclo [4.4.0.1^{2,5}.1^{7,10}] dodec-3-ene, and

8-methyl-8-t-butoxycarbonylmethoxycarbonyltetracyclo [4.4.0.1^{2,5}.1^{7,10}]dodec-3-ene.

11. (Previously Presented) A radiation-sensitive resin composition comprising (A) an acid-labile group-containing resin having a recurring unit (IV) represented by the following formula (5) and (B) a photoacid generator:



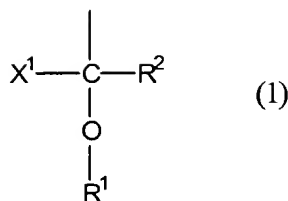
wherein R¹ represents a hydrogen atom, a monovalent acid-labile group, an alkyl group having 1-6 carbon atoms which does not have an acid-labile group, or an alkylcarbonyl group having 2-7 carbon atoms which does not have an acid-labile group, X¹ represents a linear or branched fluorinated alkyl group having 1-4 carbon atoms, R² represents a hydrogen atom, a linear or branched alkyl group having 1-10 carbon atoms, or a linear or branched fluorinated alkyl group having 1-10 carbon atoms, R⁸, R⁹, and R¹⁰ individually represents a hydrogen atom or a linear or branched alkyl group having 1-4 carbon atoms, a monovalent oxygen-containing polar group, or a monovalent nitrogen-containing polar group, n is an integer of 0-2, and m is an integer of 0-3.

12. (Previously Presented) The radiation-sensitive resin composition according to Claim 5, wherein the photoacid generator of component (B) is at least one compound selected from the group consisting of an onium salt compound, halogen-containing compound, diazoketone compound, sulfone compound, and sulfonic acid compound.

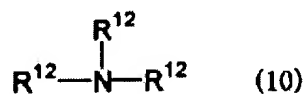
13. (Previously Presented) The radiation-sensitive resin composition according to Claim 5, further comprising a nitrogen-containing organic compound as an acid diffusion controller.

14. (Previously Presented) A radiation-sensitive resin composition comprising (A) an acid-labile group-containing resin having a structure represented by the following formula (1); (B) a photoacid generator; and (C) a nitrogen containing organic compound as an acid diffusion

controller:



wherein R¹ represents a hydrogen atom, a monovalent acid-labile group, an alkyl group having 1-6 carbon atoms which does not have an acid-labile group, or an alkylcarbonyl group having 2-7 carbon atoms which does not have an acid-labile group, X¹ represents a linear or branched fluorinated alkyl group having 1-4 carbon atoms, and R² represents a hydrogen atom, a linear or branched alkyl group having 1-10 carbon atoms, or a linear or branched fluorinated alkyl group having 1-10 carbon atoms and wherein the nitrogen-containing organic compound selected from the group consisting of a compound shown by the following formula (10), a compound having two nitrogen atoms in the molecule, a polyamino compound or polymer having three or more nitrogen atoms, a quaternary ammonium hydroxide compound, an amide group-containing compound, a urea compound, and a nitrogen-containing heterocyclic compound.



wherein R¹² individually represents a hydrogen atom, a substituted or unsubstituted, linear, branched, or cyclic alkyl group, substituted or unsubstituted aryl group, or substituted or unsubstituted aralkyl group.

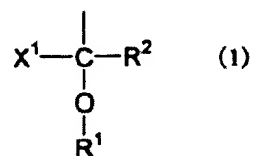
15. (Previously Presented) The radiation-sensitive resin composition according to Claim 5, further comprising an alicyclic additive having an acid-labile organic group.

16. (Original) The radiation-sensitive resin composition according to Claim 15, wherein the alicyclic additive is at least one compound selected from the group consisting of an

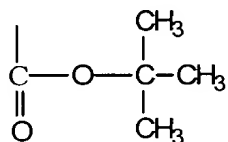
adamantane derivative, a deoxycholate, a lithocholate, and 2,5-dimethyl-2,5-di (adamantylcarbonyloxy)hexane.

17. (Cancel)

18. (Previously Presented) A radiation-sensitive resin composition comprising (A) an acid-labile group-containing resin having a structure represented by the following formula (1) and (B) a photoacid generator:

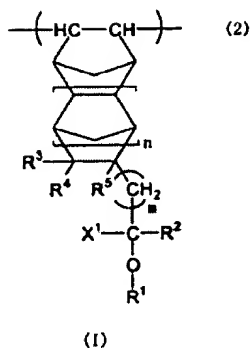


wherein R¹ is a methyl group or a moiety represented by the following structure:



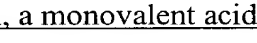
X¹ represents a linear or branched fluorinated alkyl group having 1-4 carbon atoms, and R² represents a hydrogen atom, a linear or branched alkyl group having 1-10 carbon atoms, or a linear or branched fluorinated alkyl group having 1-10 carbon atoms.

19. (Currently Amended) A radiation-sensitive resin composition comprising (A) an acid-labile group-containing resin and (B) a photoacid generator, wherein the acid-labile group-containing resin comprises a recurring unit (I) represented by the following formula (2):



wherein R¹ represents a monovalent acid-labile group, an alkyl group having 1 - 6 carbon atoms which does not have an acid-labile group, or an alkylcarbonyl group having 2 - 7 carbon atoms which does not have an acid-labile group, X¹ represents a linear or branched fluorinated alkyl group having 1-4 carbon atoms, and R² represents a hydrogen atom, a linear or branched alkyl group having 1-10 carbon atoms, or a linear or branched fluorinated alkyl group having 1-10 carbon atoms and wherein each of R³, R⁴, and R⁵ individually represent a hydrogen atom or a linear or branched alkyl group having 1 - 4 carbon atoms, a monovalent oxygen-containing polar group, or a monovalent nitrogen-containing polar group, n is an integer of 0 - 2, and m is an integer of 0 - 3.

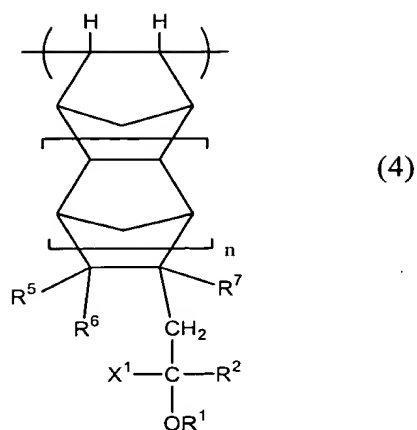
Claims 20-21. Cancel



23 - 24 (Cancel)

25. (Previously Presented) A radiation-sensitive resin composition comprising

(4),

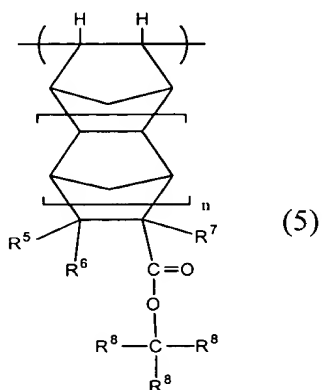


wherein R^1 represents a hydrogen atom or a monovalent acid-labile group, X^1 represents a linear or branched fluoroalkyl group having 1-4 carbon atoms, and R^2 represents a hydrogen atom, a linear or branched alkyl group having 1-10 carbon atoms, or a linear or branched fluorinated alkyl group having 1-10 carbon atoms, and R^5 , R^6 , and R^7 individually represent a hydrogen atom, a linear or branched alkyl group having 1-4 carbon atoms, a monovalent oxygen-containing polar group, or a monovalent nitrogen-containing polar group, and n is an integer of 0-2,

wherein all recurring units forming the resin are derived from a norbornene derivative or a tetracyclododecene derivative, and

(B) a photoacid generator.

26. The radiation-sensitive resin composition according to Claim 25, wherein the acid-labile group-containing resin (A) further comprises a recurring unit of the following formula (5),

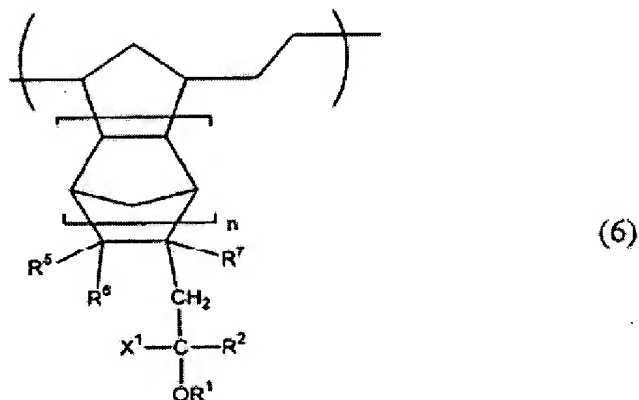


wherein R^5 , R^6 and R^7 individually represent a hydrogen atom, a linear or branched alkyl group having 1-4 carbon atoms, a monovalent oxygen-containing polar group, or a monovalent nitrogen-containing polar group, n is an integer of 0-2, and wherein each R^8 individually represents a linear or branched alkyl group having 1-4 carbon atoms or a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, or any two of the R^8 groups form, in combination and together with the carbon atom with which these groups bond, a divalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof with the remaining R^8 group being a linear or branched alkyl group having 1-4 carbon atoms or a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof.

27. (Previously Presented) A radiation-sensitive resin composition comprising,

(A) an acid-labile group-containing resin having a recurring unit of the following formula

(6),



wherein R^1 represents a hydrogen atom or a monovalent acid-labile group, X^1 represents a linear or branched fluoroalkyl group having 1-4 carbon atoms, and R^2 represents a hydrogen atom, a linear or branched alkyl group having 1-10 carbon atoms, or a linear or branched fluorinated alkyl group having 1-10 carbon atoms, and wherein R^5 , R^6 and R^7 individually represent a hydrogen

atom, a linear or branched alkyl group having 1-4 carbon atoms, a monovalent oxygen-containing polar group, or a monovalent nitrogen-containing polar group, n is an integer of 0-2,

the resin being synthesized by metallocene polymerization and a hydrogenation reaction,
and

(B) a photoacid generator.

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30. (Previously Presented) The radiation-sensitive resin composition according to Claim 25, wherein R¹ in the formula (1) is a hydrogen atom and both X¹ and R² in the formula (1) are trifluoromethyl groups.

31. (Currently Amended) The radiation-sensitive resin composition according to Claim 27, wherein R¹ in the formula (1) is a hydrogen atom and both X¹ and R² in the formula (1) are trifluoromethyl groups.